



ARRADIANCE®

ALD Nanofilm microchannel plate Technology

N. T. Sullivan



Outline

- ◀ Microchannel plate (MCP) background
- ◀ Key MCP film performance Metrics
- ◀ MCP functional thin film technology
 - ◀ Secondary electron emissive films
 - ◀ Conductive films
- ◀ Application examples
 - ◀ Large area, high aspect ratio detectors
 - ◀ High Energy Physics
 - ◀ Fast neutron detection
- ◀ Summary

What is a Micro Channel Amplifier?

Very Fast – Very Low Noise - Charged Particle Amplifier

Single Micro Channel Amplifier
(Pore ~ 0.002 mm in diameter)

Amplification (SE Cascade)

Electrons are
accelerated

Strike a surface
This creates > 1
electron

The process is
repeated along the
length of the pore

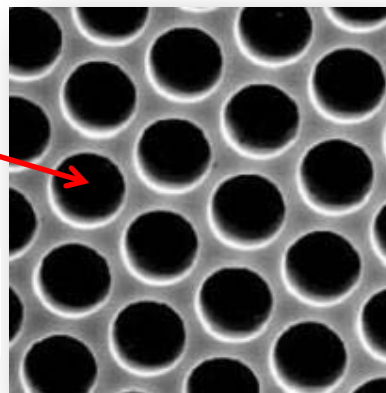
Input Electron

Bias Voltage
1000 V

High Gain up to $1e6$

Low noise – Very fast pico second response

Micro Channel Plate
(MCP -Array of pores)

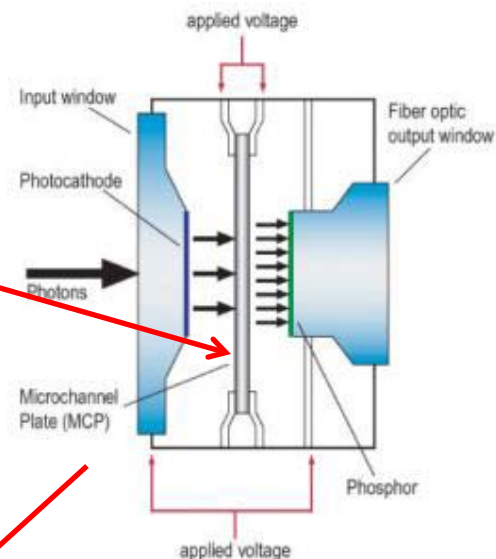


*pore diameter ranges from 5-10
um in with an AR of >50:1*

Finished NV Tube



Micro Channel Plate
Used In Light Amplification



NV Application



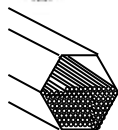
Critical MCP processing



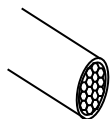
1" Etch-able Core
Lead Glass Rod



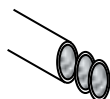
Draw Tower



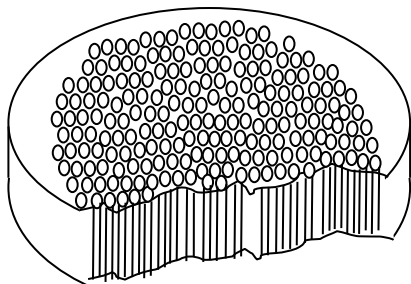
Stacked
Draw Tower
Repeated



Boule
5-100mm Dia



Diced
0.2-0.3 mm thick



Etched
Producing >5M
2-10 um pores

TABLE 2

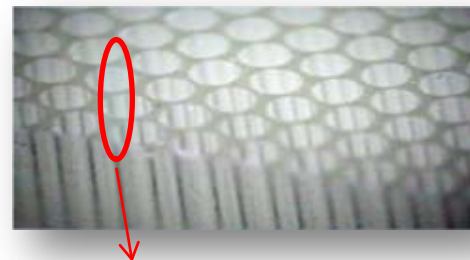
Elemental composition of MCP glass^a.

| Z | Element | Weight percent |
|----|---------|----------------|
| 82 | Pb | 47.8 |
| 8 | O | 25.8 |
| 14 | Si | 18.2 |
| 19 | K | 4.2 |
| 37 | Rb | 1.8 |
| 56 | Ba | 1.3 |
| 33 | As | 0.4 |
| 55 | Cs | 0.2 |
| 11 | Na | 0.1 |

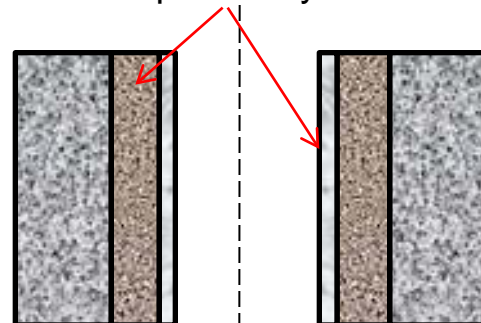
^a Density – 4.0 g./cm³.

Wiza, Nuclear Inst. & Meth., Vol 162, 1979, 587

Substrate Functionalize



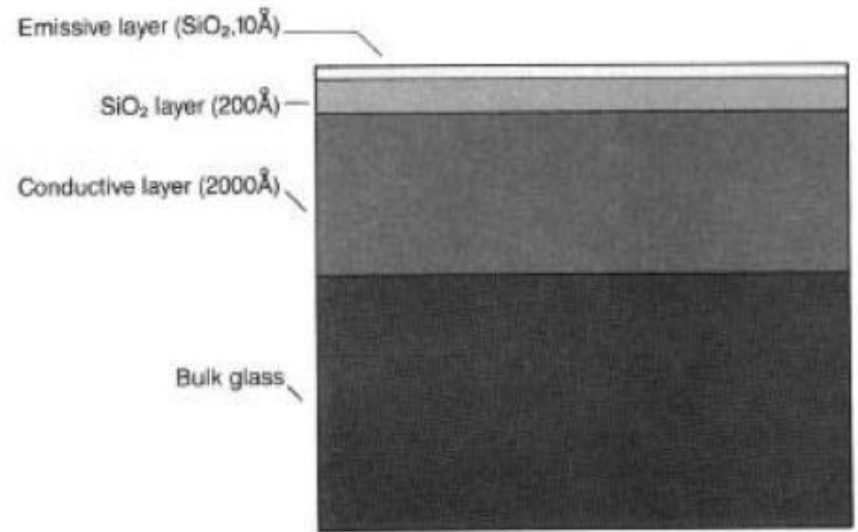
H₂ Reduction conduction & emission layers
produced simultaneously & cannot be
optimized independently



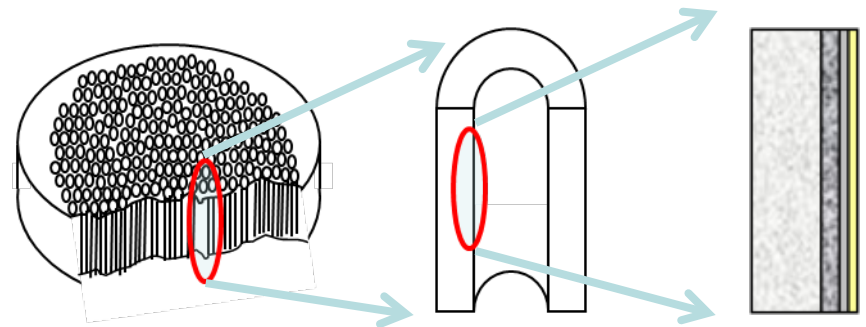
Alternative MCP Substrates: Key Findings

- ◆ Substrate
 - ◆ Mechanical structure
 - ◆ Electrically insulating
- ◆ Conductive layer
 - ◆ Conformal & uniform
 - ◆ $\sim 10^{14}$ Ohms/Sq
 - ◆ Low field effect
- ◆ Emissive layer
 - ◆ Conformal & uniform
 - ◆ High secondary yield
- ◆ MCP Device
 - ◆ High Gain
 - ◆ Resistance stability and matching
 - ◆ Stable gain following "scrub"

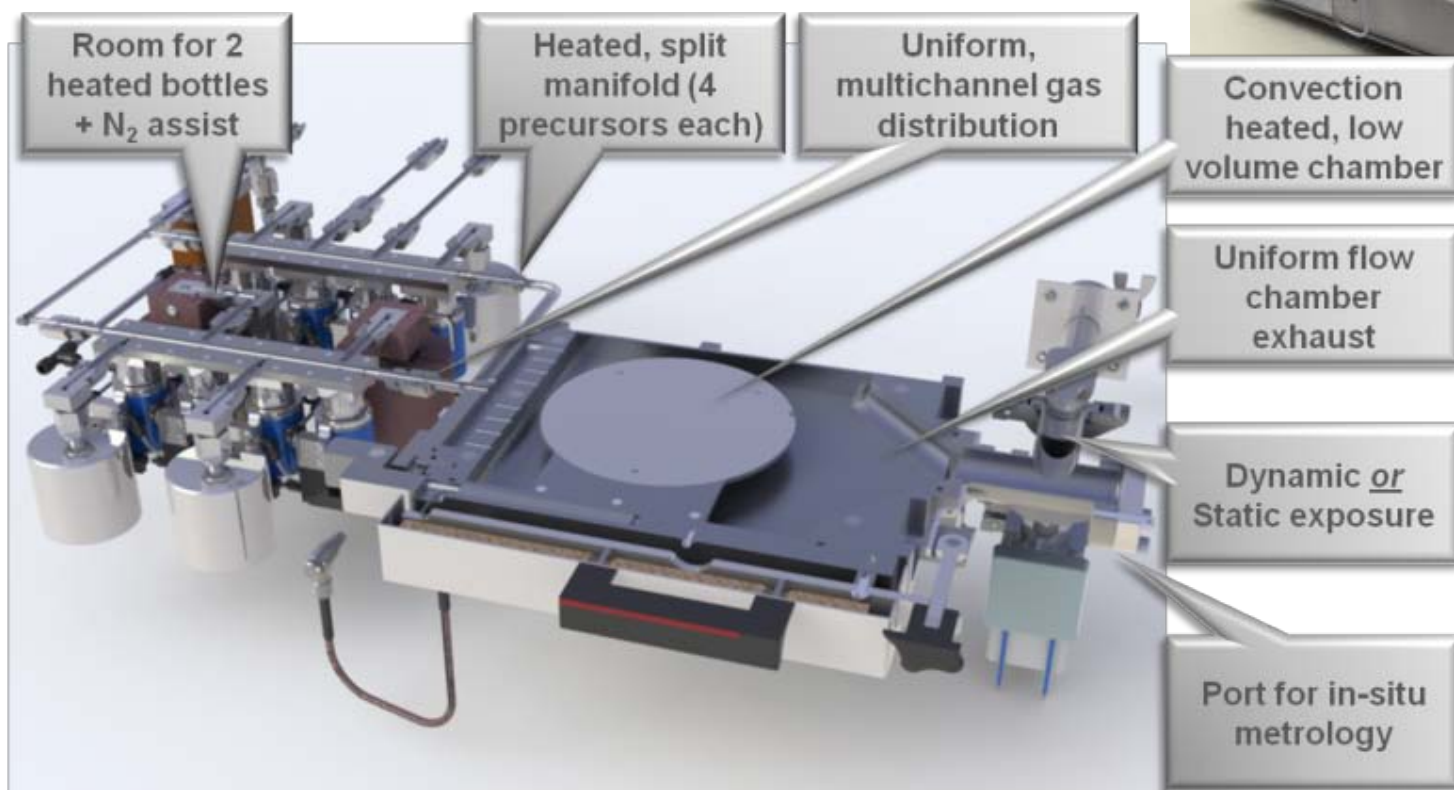
MCP performance tied to glass composition



Channeltron electron multiplier handbook (Burle)

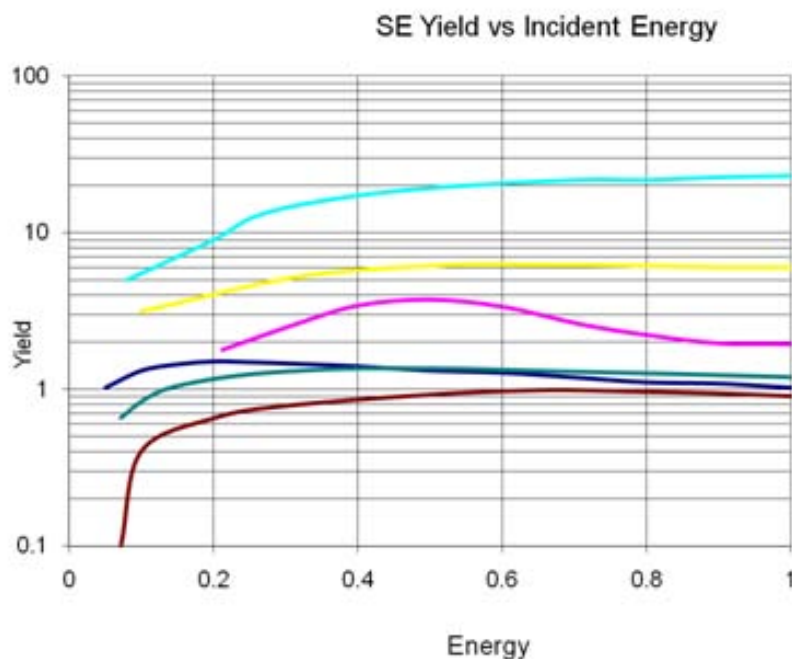


Experimental: GEMStar 8 Equipment

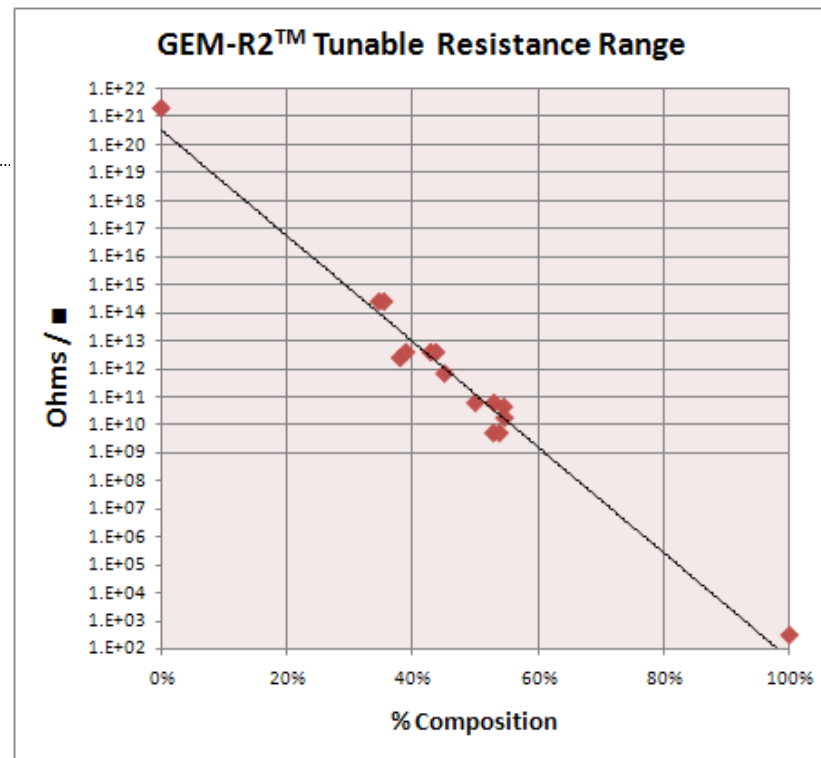


- ◆ Designed for extreme surface area, high aspect ratio structures: Multi-channel precursor delivery system isolates & distributes precursors combine with a tapered exhaust to provide exceptional nanofilm uniformity.
- ◆ Differentially pumped system seals eliminate gas permeation which along with separate and actively heated Oxidant and Metal-Organic manifolds eliminate parasitic nanofilm production.
- ◆ Metrology Interface for QCM, ellipsometry, FTIR, OES and room for up to six high capacity precursor cylinders (2 heated) with 2 independent gas lines, maximizes system productivity.

Layer materials and properties



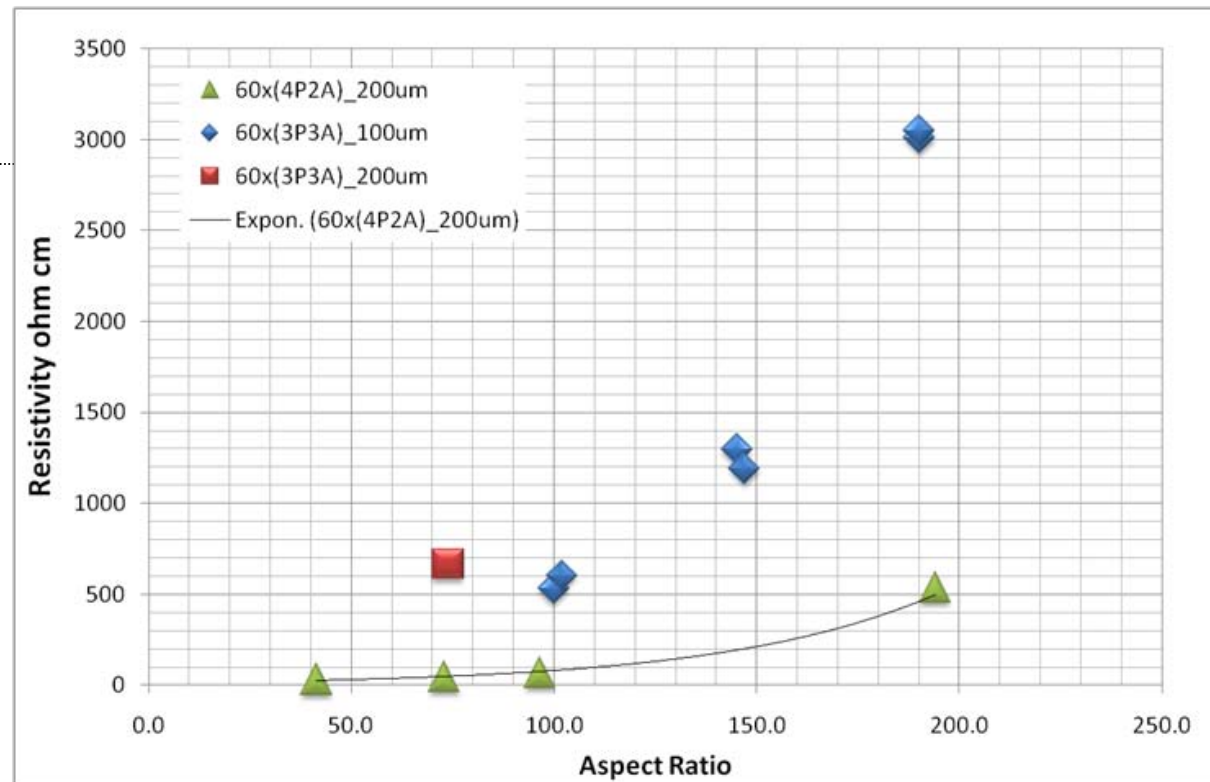
- ◆ Emissive nanofilms
 - ◆ Thin, conductively doped Al_2O_3
 - ◆ Thin MgO
 - ◆ Thin $\text{MgO} - \text{TiO}_2$ nanolaminate
- ◆ ALD enables wide range of material selection
- ◆ SE yields range from ~1 to ~5 in energy region of interest
- ◆ MCP Pb-glass SE yield ~1-2



- ◆ Conductive nanofilms
 - ◆ Zn doped CuO nanolaminate with alternating layers of Al_2O_3
 - ◆ Pt nanoclusters formed within an Al_2O_3 nanoalloy
- ◆ Conductivity control over 7 orders
- ◆ Ohmic conduction
- ◆ Stable resistance in the presence of applied field
- ◆ TCR < 1% - comparable to Pb-glass MCP values

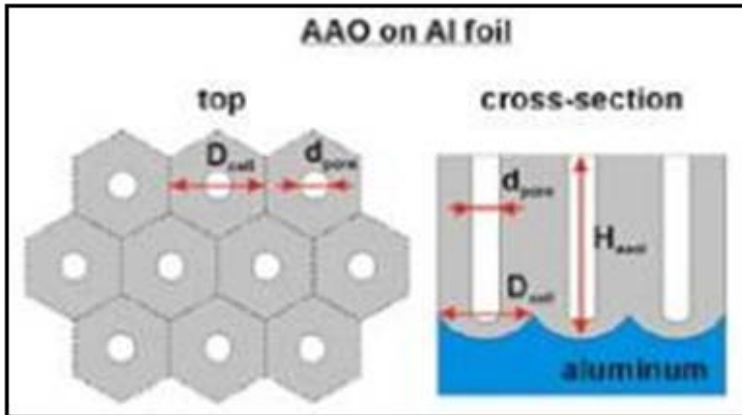
Process characterization

- Electrical - AR Penetration of conducting film into fiber optic structures of constant diameter & varying length.



- Mechanical - using specialized fiber optics and index matching, optically locating the depth of penetration. Internal fiber diameter (pore width) is $14.9\mu\text{m}$ and the length of penetration is measured to be $4803\mu\text{m}$, resulting in AR coverage of 322:1.

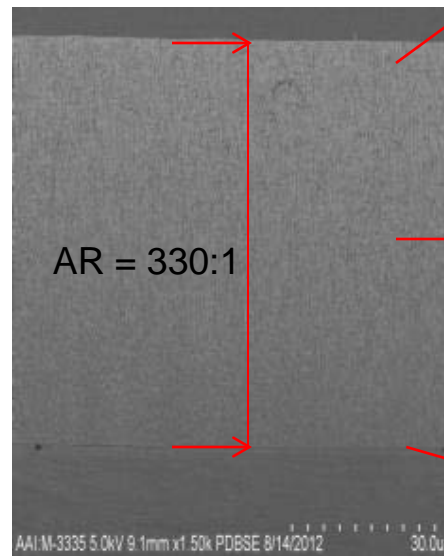
Nanofilm on AAO test structure



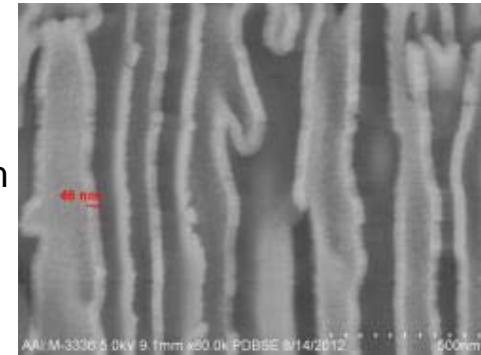
Backscatter SEM – nanofilm highlighted on AAO

AAO:

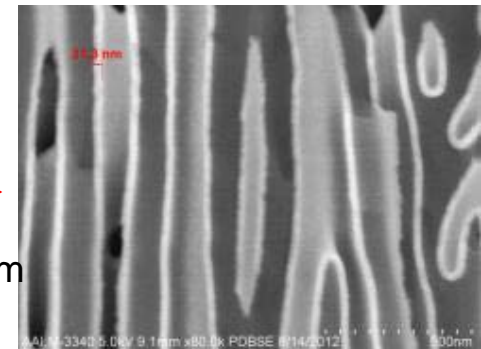
- ◀ Pores $50\ \mu\text{m} \times 150\text{nm}$ double sided
- ◀ Surface area $1.3\ \text{m}^2$



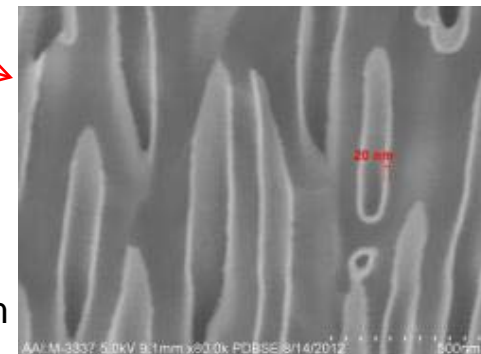
46nm



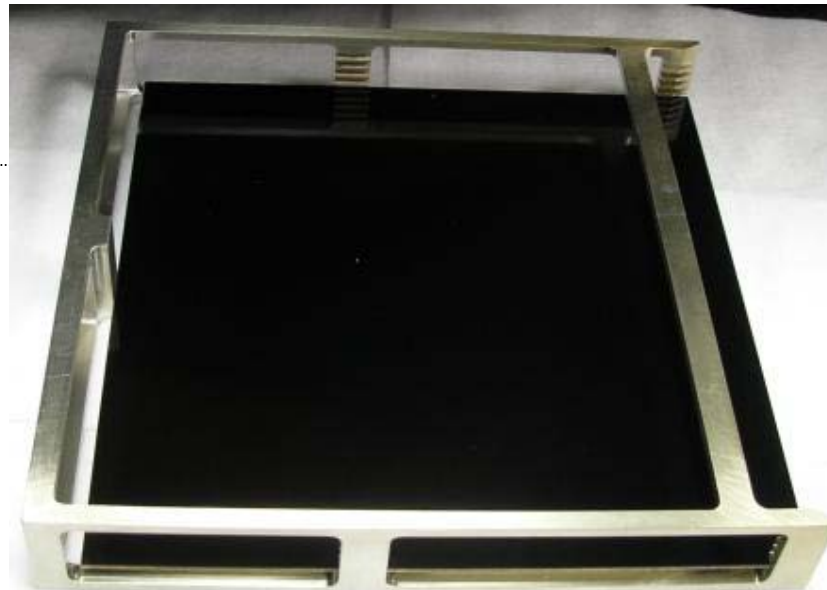
32nm



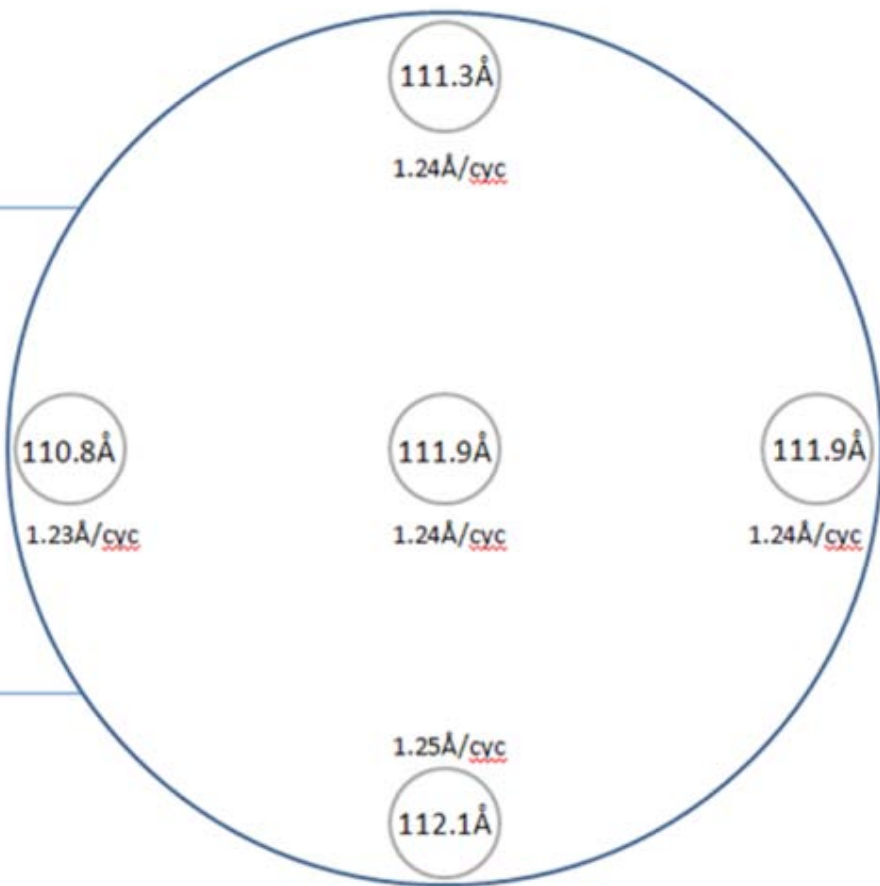
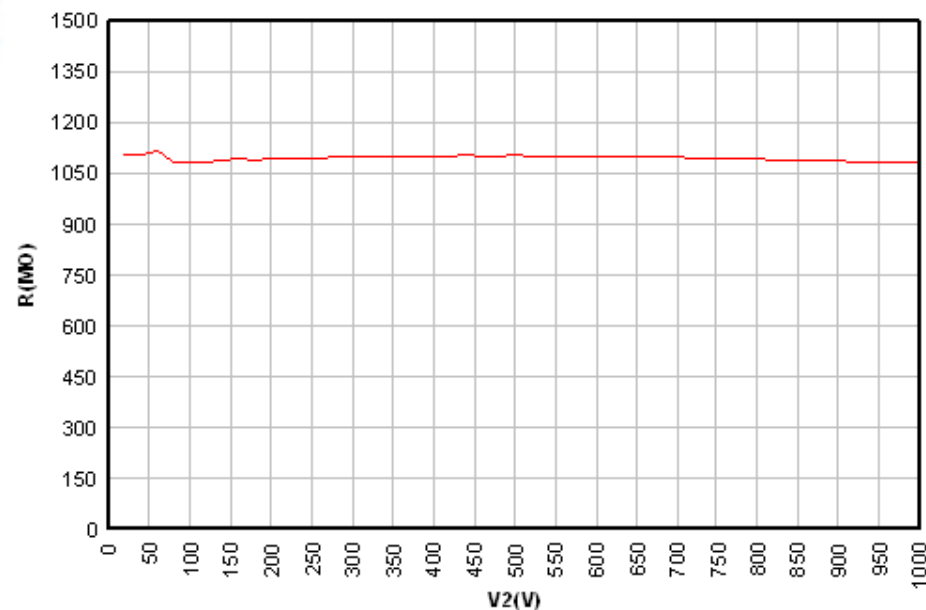
20nm



Large Area MCP results



MCP R vs V2
S001316- <INC-GCA-D25-P20-L60-O60-B8-NR>
MetData™ MCP Data Analysis (3.0.7)



MCP Gain Lifetime

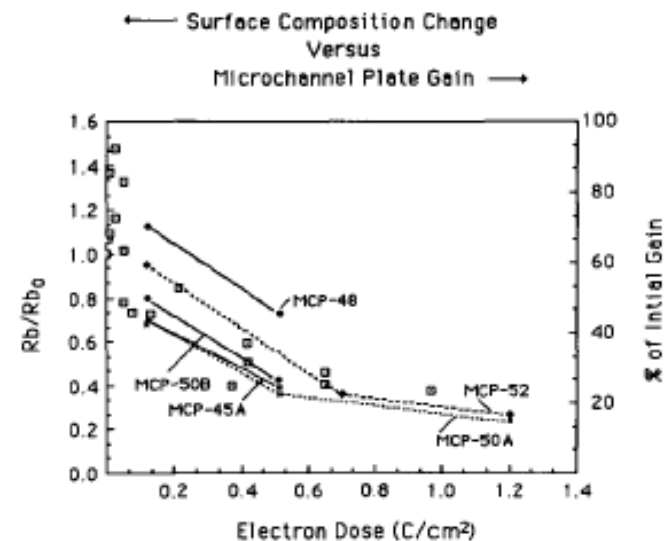
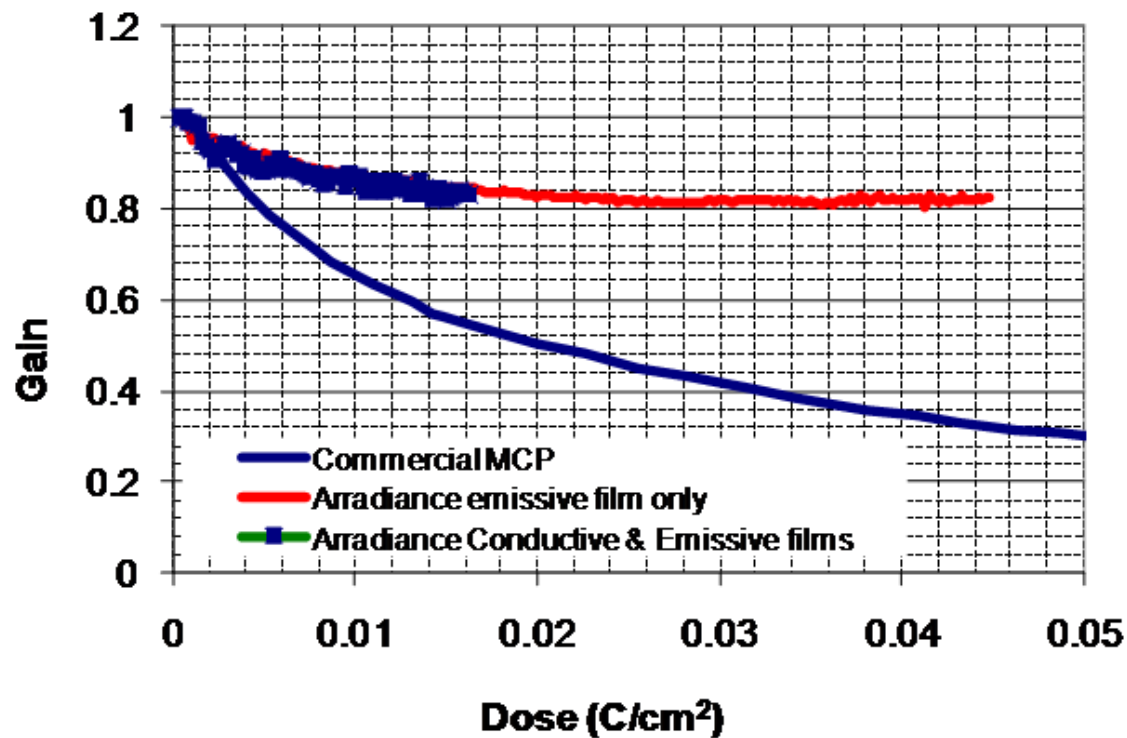
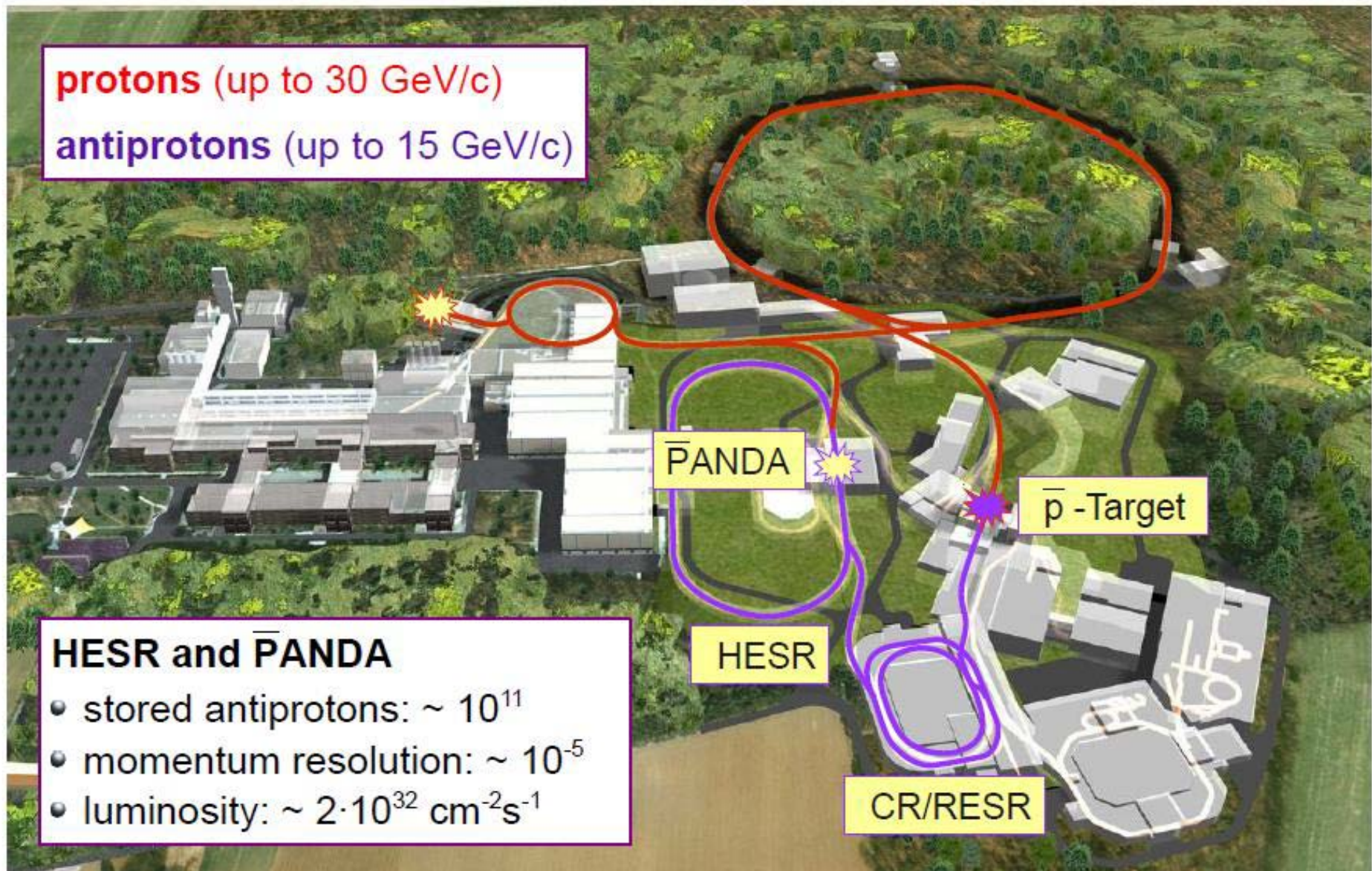


Fig. 7. The dose-dependent changes in the gain of various MCP devices (solid connected points), and the Rb surface concentration on acid-etched and reduced fracture surfaces (open points); the MCPs and the fracture surfaces are (Cs, Rb)-lead silicate.

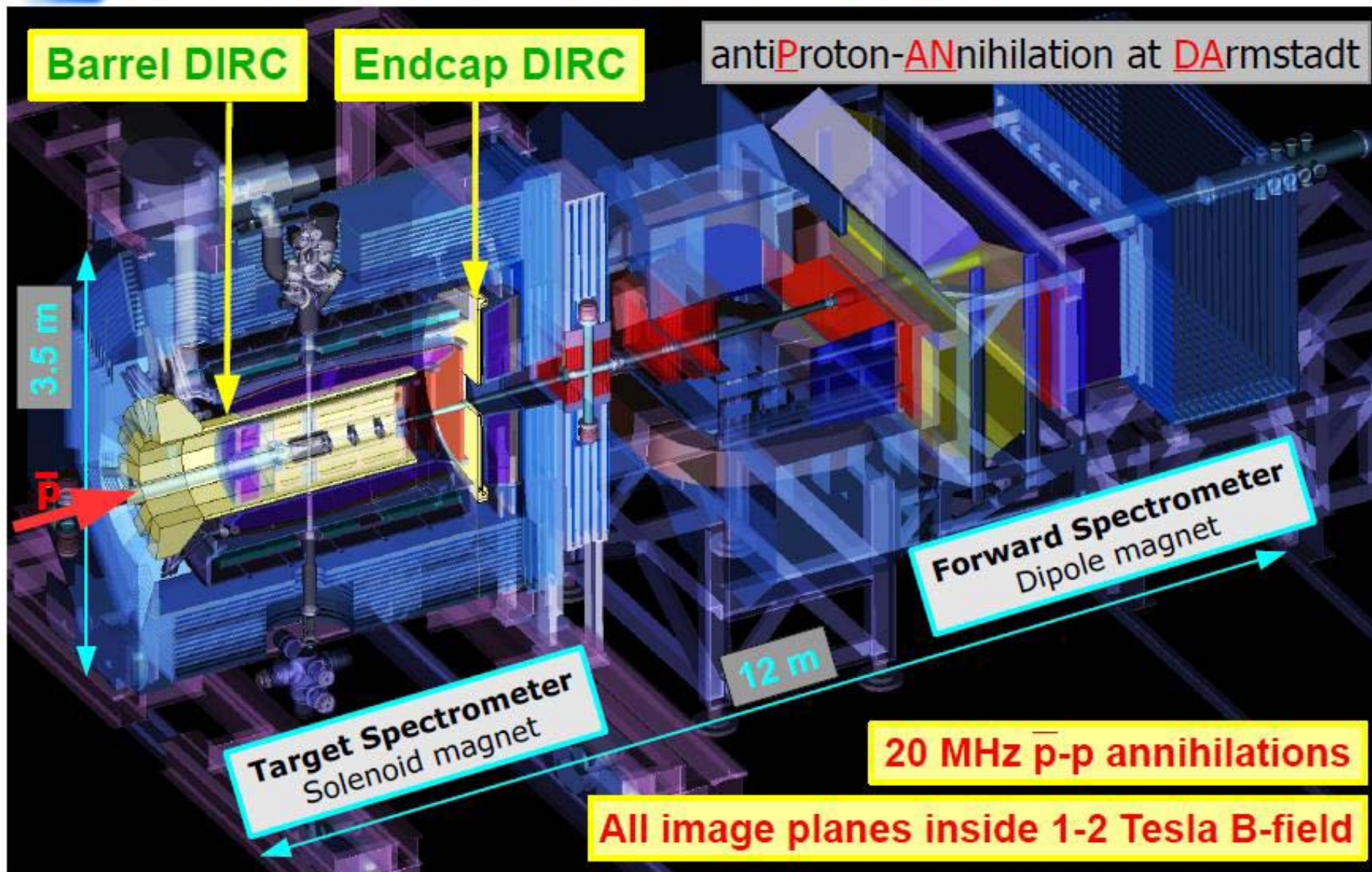
A.M. THEN and C.G. PANTANO Journal of Non-Crystalline Solids 120 (1990) 178-187

Antiproton Facility HESR at FAIR





PANDA Detector at FAIR





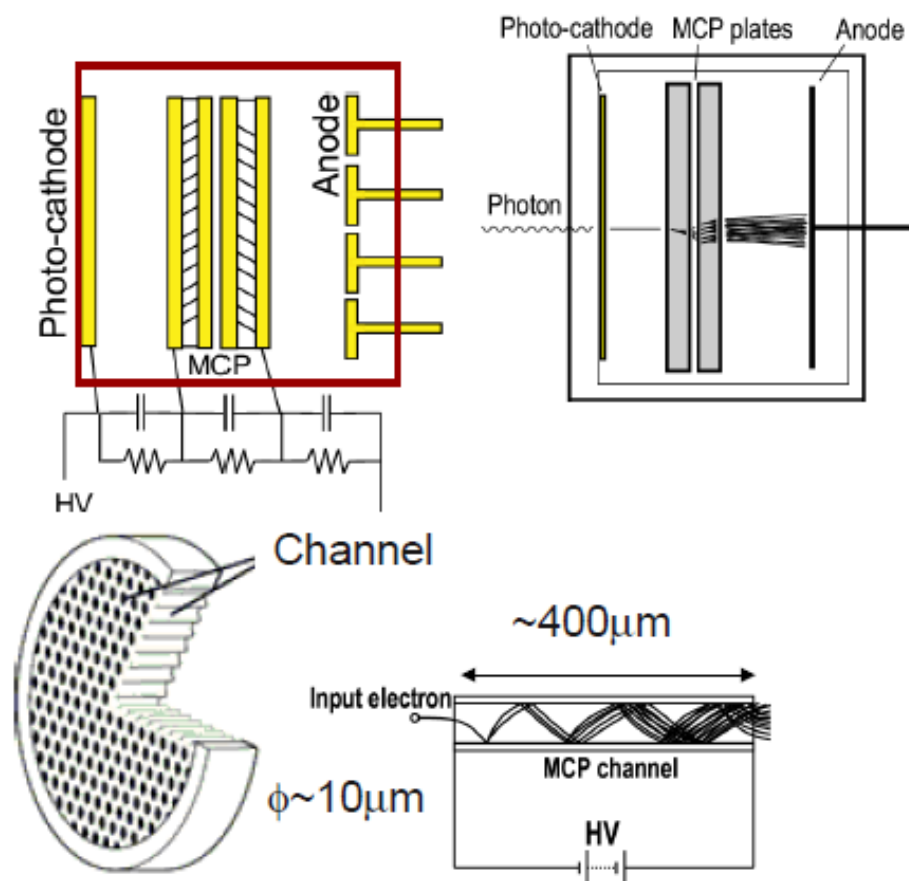
Challenges to Photon Sensors

- Good geometrical resolution over a large surface
 - **multi-pixel sensors** with $\sim 5 \times 5 \text{ mm}^2$ anodes
- Single photon detection inside B-field
 - **high gain** ($> 5 \times 10^5$) in up to 2 Tesla
- Time resolution for ToP and/or dispersion correction
 - **very good time resolution** of $< 100 \text{ ps}$ for single photons
- Few photons per track
 - **high detection efficiency** $\eta = \text{QE} * \text{CE} * \text{GE}$
[QE = quantum efficiency; CE = collection efficiency; GE = geometrical efficiency]
 - **low dark count rate**
- Photon rates in the MHz regime
 - **high rate capability** with rates of several MHz/cm^2
 - **long lifetime** with integrated anode charge of $1\text{-}5 \text{ C/cm}^2/\text{y}$



Microchannel-Plate PMT

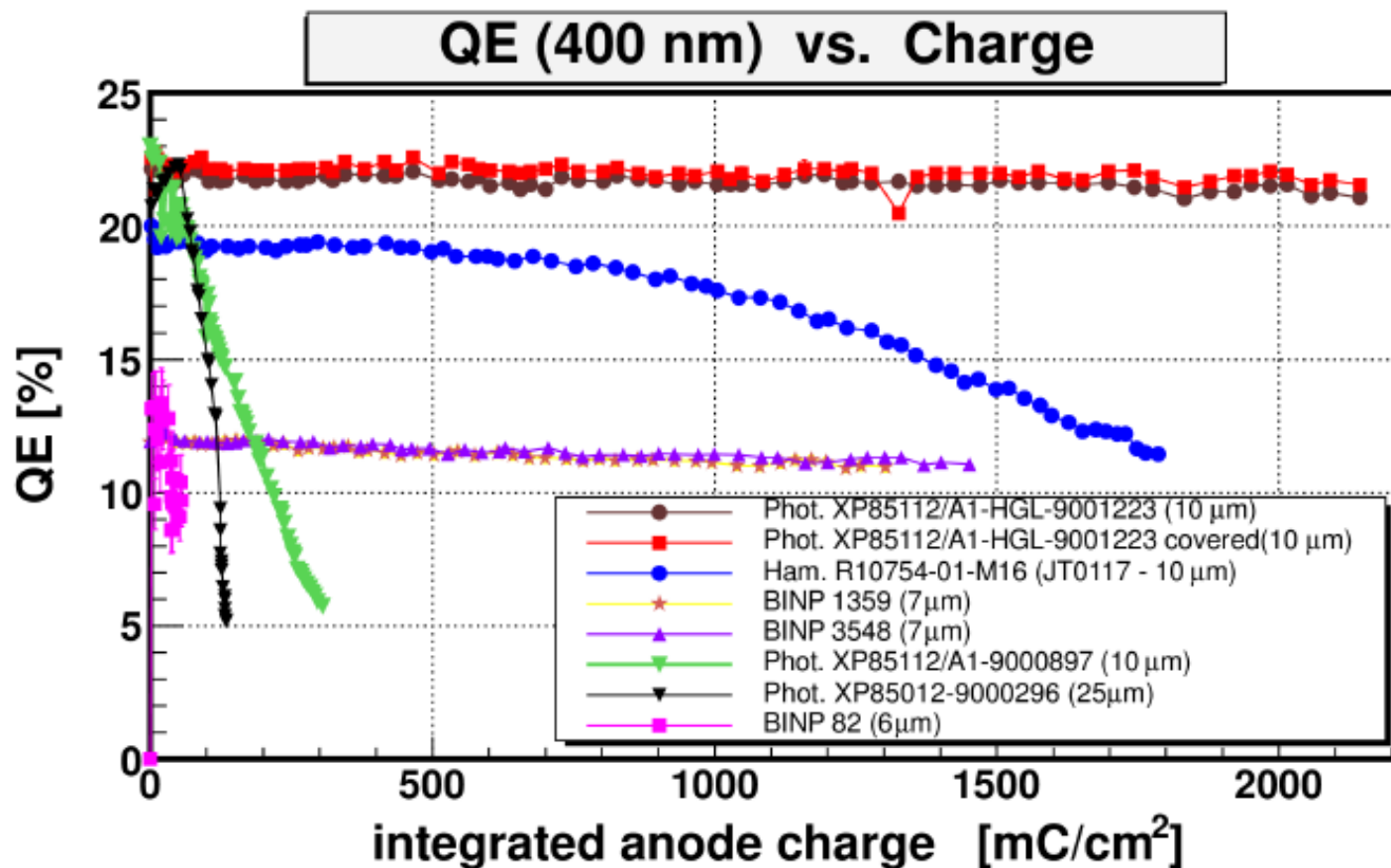
electron multiplication in glass capillaries ($\varnothing \approx 10\text{-}25\ \mu\text{m}$)



- usable in high magnetic fields
- high gain:
 - $>10^6$ with 2 MCP stages
 - single photon sensitivity
- very fast time response:
 - signal rise time = 0.3 – 1.0 ns
 - TTS < 50 ps
- low dark count rate
- quantum efficiency comparable to that of standard vacuum PMTs
- multi-anode PMTs available
- caveats:
 - lifetime (QE drops)
 - price



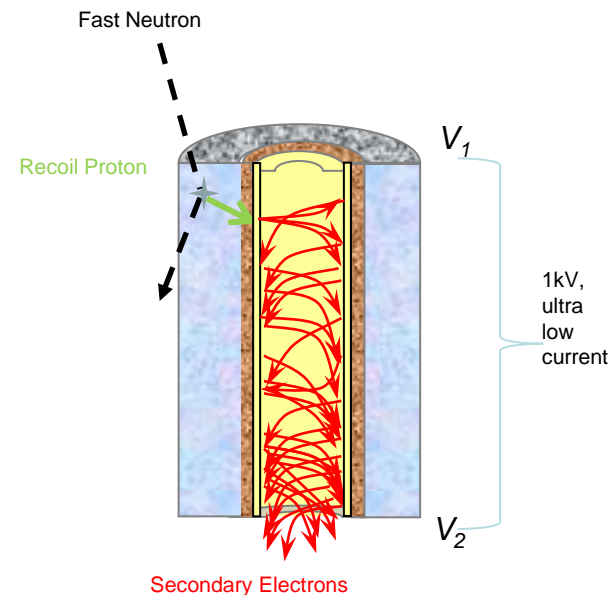
Lifetime of Different MCP-PMTs



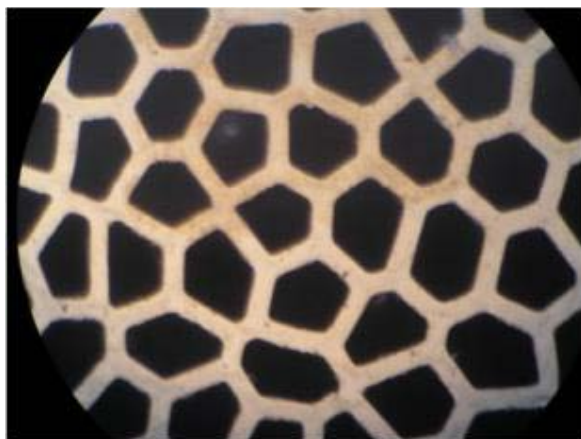
- older BINP and PHOTONIS MCP-PMTs: rapid Q.E. degradation
- new PHOTONIS XP85112: **still no Q.E. drop at $>2 \text{ C}/\text{cm}^2$**

SNM detection technology overview

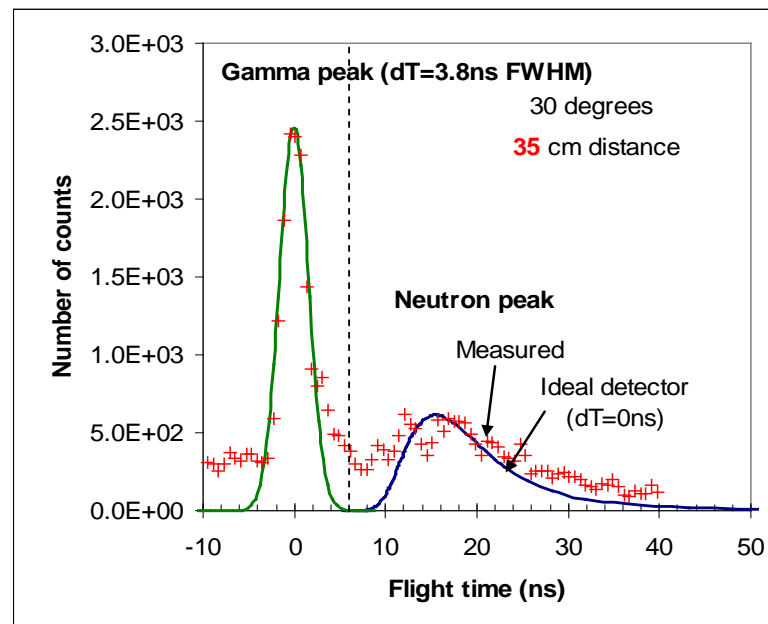
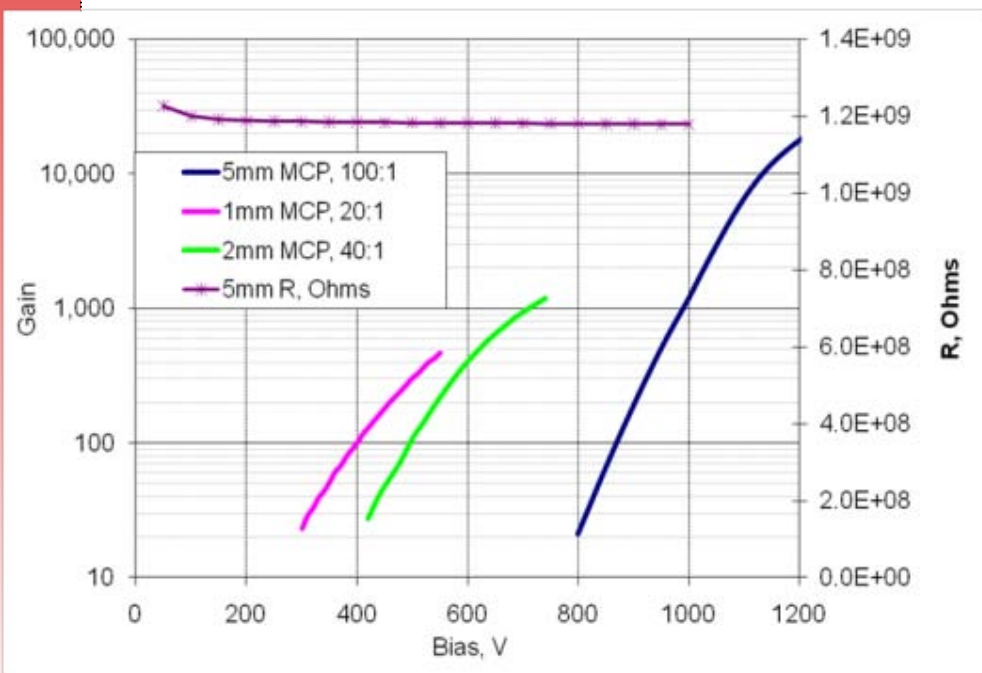
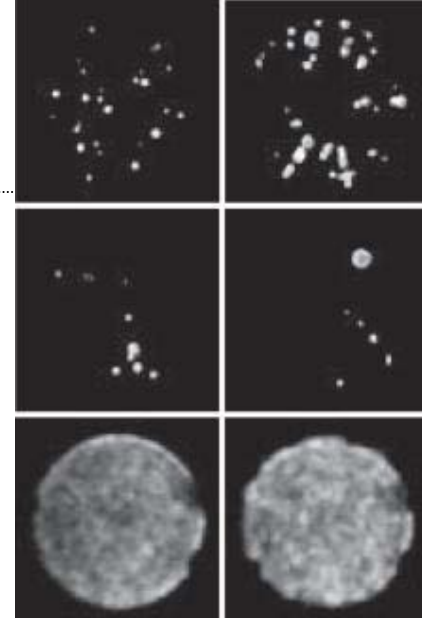
- ◆ Hydrogen-rich PMMA microchannel structure
- ◆ Graded Temperature ALD deposition
 - ◆ Active films deposition at 140C
- ◆ Neutron-proton recoil reaction within plastic at better than 1% efficiency
- ◆ Proton initiated secondary electron cascade
- ◆ Output pulse $10^3 - 10^6$ electrons
- ◆ Standard readout electronics
- ◆ Technology is scalable to large format



Plastic substrate MCP



Phosphor screen images of events detected with Co-60 gamma source (left) and Cf-252 gamma and neutron source (right).



Timing histogram of time delta between two detectors in response to Co-60 and Cf-252 sources.



Summary

- ◀ Emission and conduction layers for MCP technology have been developed
- ◀ Emission layer improves the performance of glass MCPs
 - ◀ High gain
 - ◀ Longer lifetime
 - ◀ Reduced outgassing / ion feedback
- ◀ Substrate independent conduction and emission films open new possibilities
 - ◀ Large area micromachined and plastic substrates
 - ◀ Temperature compatibility over a wide range
 - ◀ Novel photocathode materials/configurations
 - ◀ Low noise – no radioactive traces
 - ◀ Better uniformity / reproducibility / spatial resolution